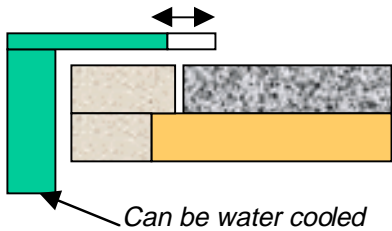
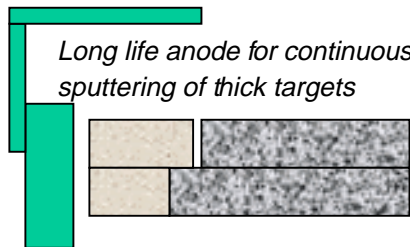


**Mechanical Aspects**



Long life anode for continuous sputtering of thick targets



Continuous operation option

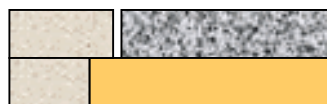


Chamber flange

Lower cost anode option



Chamber flange



Note: The anode is always an integral part of the magnetic field design and should always be application specific

**GENCOA**

The Importance of anodes



Removable top anode strip

Target / backing plate clamp

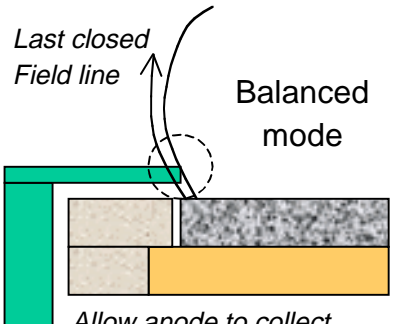
Thick Walled Side anode

Diaphragm clamp

target

Backing plate / target material

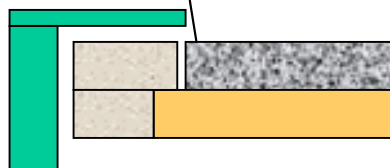
**DC sputtering**



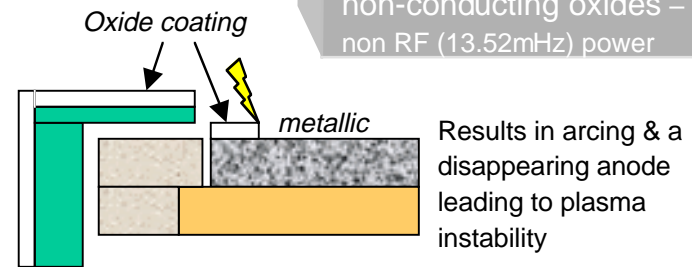
Allow all electrons to escape the magnetron plasma

Last closed Field line

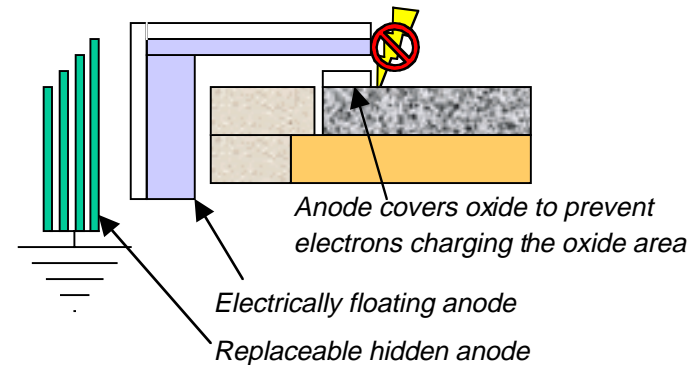
Unbalanced mode



Reactive sputtering of non-conducting oxides – non RF (13.52MHz) power



Single cathode solution



2<sup>nd</sup> solution – use 2 magnetrons with AC or MF power; see Gencoa AS magnetrons  
3<sup>rd</sup> solution – Gencoa's new full face (FFE) erosion magnetrons – no oxide on target